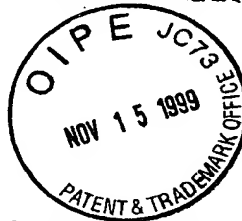


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#3REISSUE PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Broadening Reissue Application of

Osamu TANITSU, Takashi MORI
and Noriaki YAMAMOTO

Application No.: 09/326,214 (Reissue Application of U.S. Patent No. 5,636,003 issued June 3, 1997 (U.S. Patent Application Serial No. 08/365,532 filed December 28, 1994))

Filed: June 3, 1999

Docket No.: 103512.99

For: ILLUMINATION OPTICAL APPARATUS
AND SCANNING EXPOSURE APPARATUSREISSUE DECLARATIONAssistant Commissioner for Patents
Washington, D.C. 20231

Sir:

We, Osamu TANITSU, Takashi MORI and Noriaki YAMAMOTO, hereby declare that:

1. We are citizens of Japan with the addresses as stated below next to our names.
2. We have reviewed and understand the contents of the specification and claims of the above-captioned reissue application, including the claims in the Preliminary Amendment filed September 2, 1999, and this reissue declaration.
3. We believe that we are the original and joint inventors of the invention described and claimed in the reissue application and in U.S. Letters Patent No. 5,636,003, which issued from U.S. Patent Application No. 08/365,532 filed December 28, 1994, which is a Continuation-in-Part of U.S. Patent Application No. 08/147,259 filed November 4, 1993.
4. We claim the priority benefits of the following applications: Japanese Patent Application No. 4-295458, filed November 5, 1992, Japanese Patent Application No. 5-

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019098, filed February 5, 1993 and Japanese Patent Application No. 6-051490, filed March 23, 1994.

5. We acknowledge our duty to disclose information which is material to the examination of this reissue application in accordance with 37 C.F.R §1.56(a).

6. We consider U.S. Patent No. 5,636,003 to be partly inoperative by reason of claiming less than we had a right to claim because the original claims are unduly limited and may not provide an adequate scope of protection.

7. Patent claim 41 relates to a scanning exposure apparatus comprising:

- a light supply means for supplying a beam;
- a light-source-image forming means for forming a plurality of light source images in a substantially linear arrangement, based on the beam from said light supply means;
- and internal reflection type integrator having two reflection planes parallel to each other for forming a plurality of light source images, based on the beam from said light-source-image forming means, said internal reflection type integrator have a rectangular cross section, two sides adjacent to each other of said rectangular cross section being different in length;
- a relay optical system disposed between said light-source-image forming means and said internal reflection type integrator, for making a position of the light source images formed by said light-source-image forming means conjugate with a position of the light source images formed by said image reflection type integrator;
- a condenser optical system for condensing the beam from said internal reflection type integrator to illuminate a surface of a reticle;

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- a reticle stage for moving said reticle in a direction parallel to said surface of the reticle;
- a wafer stage for carrying a wafer on which integrated circuits are to be formed, and moving said wafer in a direction parallel to a surface of said wafer; and
- a projection optical system disposed between said reticle and said wafer, for making a position at which said reticle is located conjugate with a position at which said wafer is located.

However, claim 41 is unnecessarily limited in that the invention encompasses a scanning exposure apparatus including an illumination optical system having an optical axis substantially perpendicular to a rectangular area on a predetermined plane, the illumination optical system comprising an internal reflection type integrator with an exit plane having a shape substantially equal to that of the rectangular area, the illumination optical system illuminating the rectangular area with an illumination beam; and a movable member arranged to relatively move a mask with respect to the rectangular area during scanning exposure on a substrate with the illumination beam through the mask, and to hold the mask at a position on or near the predetermined plane, as now set forth in claim 43.

8. All errors being corrected in this reissue application up to the time of executing this declaration arose without any deceptive intention on our part.

9. We hereby revoke all prior powers of attorney and appoint the following as our attorneys of record with full power of substitution and revocation to prosecute this application and to transact all business in the Patent Office:

James A. Oliff, Reg. No. 27,075; William P. Berridge, Reg. No. 30,024;

Kirk M. Hudson, Reg. No. 27,562; Thomas J. Pardini, Reg. No. 30,411;

Edward P. Walker, Reg. No. 31,450; Robert A. Miller, Reg. No. 32,771;

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Mario A. Costantino, Reg. No. 33,565; and Caroline D. Dennison, Reg. No. 34,494.

All correspondence in connection with this application should be sent to Oliff & Berridge, PLC, P.O. Box 19928, Alexandria, Virginia 22320, telephone (703) 836-6400.

10. We have reviewed and understand the contents of this reissue declaration, and all statements made herein of our knowledge are true, and all statements made on information and belief are believed to be true, and further these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the U.S. Code and that such willful false statements may jeopardize the validity of the application or any patent reissued thereon.

Date: September 7, 1999

✓ Osamu Tanitsu

Osamu TANITSU,

Residence: Funabashi-shi, Chiba-ken, JAPAN

Address: c/o Nikon Corporation
2-3, Marunouchi 3-chome,
Chiyoda-ku, Tokyo, JAPAN

Date: Sept. 7, 1999

Takashi Mori

Takashi MORI

Residence: Fujisawa-shi, Kanagawa-ken, JAPAN

Address: c/o Nikon Corporation
2-3, Marunouchi 3-chome,
Chiyoda-ku, Tokyo, JAPAN

Date: Nov. 4, 1999

Noriaki Yamamoto

Noriaki YAMAMOTO

Residence: Yokohama-shi, Kanagawa-ken, JAPAN

Address: c/o Nikon Corporation
2-3, Marunouchi 3-chome
Chiyoda-ku, Tokyo, JAPAN